

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re F	atent Ap	plication of)	
Christopher C. CHANG et al.			Group Art Unit: 1773	
Application No.: 09/749,917			Examiner: N. Uhlir	
Filed: December 29, 2000			Confirmation No.: 6832	S.
For:	CHAM	CONTAMINATION PLASMA BER COMPONENTS AND ODS FOR MAKING THE SAM	Examiner: N. Uhlir Confirmation No.: 6832 CLOSURE STATEMENT	24 701
			CLOSURE STATEMENT FTAL LETTER	00
		nissioner for Patents .C. 20231		
Sir:				
above-		ed is an Information Disclosure and patent application.	Statement and accompanying form PTO-144	9 for th
	[X]	No additional fee for submission	n of an IDS is required.	
	[]	The fee of \$180.00 (126) as set	forth in 37 C.F.R. § 1.17(p) is also enclose	ed.
	[]	A certification under 37 C.F.R	§ 1.97(e) is also enclosed.	
	[]	A certification under 37 C.F.R in 37 C.F.R. § 1.17(p) are also	§ 1.97(e), and the fee of \$180.00 (126) as enclosed.	set fortl
	[]	Charge \$to Depo	sit Account No. 02-4800 for the fee due.	
	[]	A check in the amount of \$	is enclosed for the fee due.	
	6, 1.17 a		to charge any appropriate fees under 37 C. this paper, and to credit any overpayment, abmitted in duplicate.	
	•	-	Respectfully submitted,	
			Burns, Doane, Swecker & Mathis, l.l.	P.
Alexar	30x 1404 1dria, Vi 136-6620	rginia 22313-1404	By: Peter K. Skiff Registration No. 31,917	

Date: October 23, 2002